

Title (en)
Process for the preparation of difluoromethane

Title (de)
Verfahren zur Herstellung von Difluormethan

Title (fr)
Procédé de fabrication du difluorométhane

Publication
EP 0805136 B1 20010725 (FR)

Application
EP 97400754 A 19970402

Priority
FR 9605369 A 19960429

Abstract (en)
[origin: EP0805136A1] The continuous process for the preparation of difluoromethane (F32) from methylene chloride (F30) and hydrogen fluoride (HF) in the gaseous phase and in the presence of a fluorination catalyst is claimed. The reaction is effected in the presence of chlorine (Cl2), and the gaseous effluent from the reactor is distilled to separate (at the head) a flow comprising hydrogen chloride (HCl) and at least 90% of the F32, and from the base, a flow containing at least 90% of non-converted (F30, F31, and HF) reactants. F31 is chlorofluoromethane. The flow from the base is re-cycled to the reactor.

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IPC 8 full level
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C07C 17/20 (2013.01 - KR); **C07C 17/206** (2013.01 - EP US); **C07C 19/08** (2013.01 - KR); **Y02P 20/582** (2015.11 - EP US)

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